

Abstract

The invention relates to a method for imaging a mask (1) onto a substrate (2) by means of an illuminating unit (8) and an optical unit (9). The invention also relates to a device for carrying out the method. The aim of the invention is to
5 create a method and a device which enable the mask (1) and the smaller structures thereof to be imaged onto the substrate (2) in a precise manner, with high functional reliability, and which enable the distortions of the substrate (2) to be corrected. To this end, the illuminating unit (8) and the optical unit (9) are displaced in relation to the mask (1) and the substrate (2), distortions of the
10 substrate (2) are detected, and the imaging of the mask (1) is distorted according to the detected distortions by means of the optical unit (9) and is adapted to the distortions of the substrate (2).